



Batch XL

Optimized system for high efficiency solar cell (n-type)

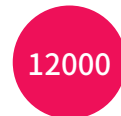
Ultra capacity batch equipment (highest cost performance)

Features & Benefit



Various batch application

- Alkaline / Acidic texturing
- pSC1 / SC2 / O₃ cleaning
- Oxidation



High throughput

- 600 wafers load
- up to 12,000w/h



Capable Si wafer size

M6 (166 x 166mm), M10 (182 x 182mm)
& M12 (210 X 210mm)



High dosing accuracy +/- 2%



Perfect Drying



Non metal component



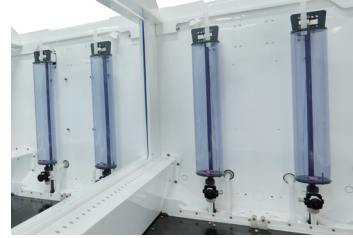
600 wafer Loading



Tilting system For perfect drying



Transport Unit



Dosing Accuracy +/- 2%

Process outline



Technical Data

| | | |
|----------------------------|---|--|
| Application | Texturing (Alkaine / Acidic), Cleaning (RCA / O ₃), Oxidation | |
| | PERC / n-PERC / TopCon / HIT / IBC | |
| Dimensions | 15,550 (L) x 2,380 (W) x 2,680 (H) mm / S.E.A. standard texturing | |
| Thoughtput & wafer loading | up to 12,000 w/h | 600 wafer loading |
| Substrate size & thickness | M6, M10 & M12 (up to 210 x 210 mm) | > 120 μm as-cut |
| Bath size | 490L for process / 310L for Rinse | |
| Temperature range | 6°C ~ 87°C | |
| Heater | Stainless steel / Quartz / Teflon coated / Electrical coil | |
| Circulation pump | Magnetic / Bellows | |
| PLC control | Mitsubishi / Allen-Bradley / Siemens | |
| Certification | CE / UL / ISO 9001 / ISO 14001 | |
| Options | Chilling system (acidic texturing) | N ₂ dry system |
| | Integrated Ozone system | MFR (Multi functional Rinse) |
| | Conductivity / pH meter | Switchable N ₂ /CDA bubbling |
| | Feed & bleed system | Extendable loading slot (18 carrier -> 36carrier) |